METHOD FOR FABRICATING A GLASS SUBSTRATE, MAGNETIC DISK, AND METHOD FOR FABRICATING THE SAME

ABSTRACT

A process for producing a glass substrate composed mainly of SiO_2 having its surface provided with a uniform microscopic streak pattern by ultraprecision polishing processing, which process includes the step of with respect to the polished glass substrate, inspecting whether a certain property of bound energy as to 2P-orbit occupying electrons of Si atom at an outermost surface portion thereof as determined by XPS is a certain specified value or below, the above certain property being an extent of shift of the bound energy or a half-value width of bound energy distribution, the above specified value being 0.10 eV or 2.15 eV, respectively.

Fig. 1